

FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO. 521		SERIAL NO. TBA	
INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)				APPLICANT Ying Ma, et al.			
				FILING DATE Herewith		GROUP TBA	

Jc986 U.S. PTO
 09/929564
 08/14/01

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>[Signature]</i>	AA 5,527,423	6/18/1996	Neville, et al.				
<i>[Signature]</i>	AB 6,063,306	5/16/2000	Kaufman, et al.				
<i>[Signature]</i>	AC 5,676,587	10/14/1997	Landers				
<i>[Signature]</i>	AD 6,001,730	12/14/1999	Farkas, et al.				
<i>[Signature]</i>	AE 6,242,351	6/5/2001	Li, et al.				
<i>[Signature]</i>	AF 09/562,298	5/1/2000	Thomas H. Baum, et al.				

FOREIGN PATENT DOCUMENTS							
DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES NO		
					X (abstract only)		
<i>[Signature]</i> AG	01/02134	11 Jan 2001	World				

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)	
<i>[Signature]</i>	AH Jianfeng Luo, et al. "Integrated Model for Chemical-Mechanical Polishing Based on A Comprehensive Material Removal Model", Sixth International Conference on Chemical-Mechanical Polish (CMP) Planarization for ULSI Multilevel Interconnection (CMP-MIC), Santa Clara, CA USA March 8-9, 2001. ✓
<i>[Signature]</i>	AI Byron J. Palla, et al., "Stabilization of High Ionic Strength Slurries Using the Synergistic Effects of a Mixed Surfactant System", Journal of Colloid and Interface Science 223, 102-111 (2000). ✓

Continue on Page

EXAMINER <i>[Signature]</i>	DATE CONSIDERED 6/16/03
--------------------------------	----------------------------

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

 OK - Considered
 Not signed